

IN THE CLAIMS:

Please CANCEL claims 100 and 101 without prejudice to or disclaimer of the recited subject matter.

Please AMEND claims 88 and 90, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1-24. (Previously Cancelled)

25. (Original) An exposure apparatus comprising:

    a chamber which incorporates an optical element and surrounds a predetermined region;

    a mechanism for setting an inert gas atmosphere in said chamber; and

    a closed vessel which surrounds said chamber,

    wherein a purity of inert gas in said chamber is higher than a purity of inert gas in said closed vessel.

26. (Original) The apparatus according to claim 25, wherein the purity of inert gas in said closed vessel is higher than a purity of inert gas outside said closed vessel.

27. (Original) The apparatus according to claim 25, wherein said mechanism discharges gas from said chamber before setting the inert gas atmosphere in said chamber.

28. (Original) The apparatus according to claim 25, wherein said closed vessel has a transmission window for transmitting light.

29. (Original) The apparatus according to claim 28, wherein the transmission window is formed from fluoride glass.

30. (Original) The apparatus according to claim 25, wherein said closed vessel has an opening/closing door.

31. (Original) The apparatus according to claim 25, further comprising a vent hole for allowing said chamber and said closed vessel to communicate with each other.

32. (Original) The apparatus according to claim 28, wherein a vent hole is freely opened/closed.

33. (Original) The apparatus according to claim 25, wherein said chamber incorporates at least some of optical elements of an illumination optical unit.

34. (Original) The apparatus according to claim 25, wherein said chamber incorporates at least some of optical elements of a projection optical unit.

35. (Original) The apparatus according to claim 25, wherein the inert gas contains at least one of helium and nitrogen.

36. (Original) The apparatus according to claim 25, wherein said chamber surrounds at least part of an optical path of light in a vacuum ultraviolet region.

37. (Original) An exposure apparatus comprising:

a chamber which incorporates an optical element and surrounds a predetermined region;

a mechanism for setting an inert gas atmosphere in said chamber; and

a closed vessel which surrounds said chamber,

wherein an internal pressure of said chamber is higher than an internal pressure of said closed vessel.

38. (Original) The apparatus according to claim 37, wherein a pressure of inert gas in said closed vessel is higher than a pressure of inert gas outside said closed vessel.

39. (Original) The apparatus according to claim 37, wherein said mechanism discharges gas from said chamber before setting the inert gas atmosphere in said chamber.

40. (Original) The apparatus according to claim 37, wherein said closed vessel has a transmission window for transmitting light.

41. (Original) The apparatus according to claim 40, wherein the transmission window is formed from fluoride glass.

42. (Original) The apparatus according to claim 37, wherein said closed vessel has an opening/closing door.

43. (Original) The apparatus according to claim 37, further comprising a vent hole for allowing said chamber and said closed vessel to communicate with each other.

44. (Original) The apparatus according to claim 43, wherein the vent hole is freely opened/closed.

45. (Original) The apparatus according to claim 37, wherein said chamber incorporates at least some of optical elements of an illumination optical unit.

46. (Original) The apparatus according to claim 37, wherein said chamber incorporates at least some of optical elements of a projection optical unit.

47. (Original) The apparatus according to claim 37, wherein the inert gas includes at least one of helium and nitrogen.

48. (Original) The apparatus according to claim 37, wherein said chamber surrounds at least part of an optical path for light in a vacuum ultraviolet region.

49-59. (Previously Cancelled)

60. (Previously Amended) A gas replacement method comprising the steps of:  
supplying inert gas into a chamber which incorporates an optical element;  
supplying inert gas into a closed vessel which surrounds the chamber; and  
controlling a purity of the inert gas in the chamber to be higher than a purity of the inert gas in the closed vessel.

61. (Original) The method according to claim 60, further comprising the step of controlling the purity of the inert gas in the closed vessel to be higher than a purity of inert gas outside the closed vessel.

62. (Previously Amended) A gas replacement method comprising the steps of:

supplying inert gas into a chamber which incorporates an optical element;  
supplying inert gas into a closed vessel which surround the chamber; and

controlling a pressure of the inert gas in the chamber to be higher than a pressure of the inert gas in the closed vessel.

63. (Original) The method according to claim 62, further comprising the step of controlling the pressure of the inert gas in the closed vessel to be higher than a pressure of inert gas outside the closed vessel.

64-75. (Previously Cancelled)

76. (Previously Added) An exposure apparatus comprising:  
a chamber which incorporates an optical element;  
a closed vessel which surrounds said chamber; and  
a pump for reducing an internal pressure of said chamber,  
wherein a pressure of said closed vessel is reduced when the internal pressure of the chamber is reduced,  
wherein said chamber is supported by a member which supports a lens barrel that holds the optical element, and  
wherein said closed vessel is coupled to the surface plate via a movable displacement adjusting member.

77. (Previously Added) The apparatus according to claim 76, wherein said movable displacement adjusting member includes a bellows.

78. (Previously Added) A device manufacturing method comprising the steps of:  
exposing a member to be processed by the exposure apparatus defined in claim 76; and  
developing the exposed member in order to manufacture the device.

79. (Previously Added) A gas replacement method comprising the steps of:  
reducing an internal pressure of a chamber which incorporates an optical element;  
reducing a pressure of a closed vessel which surrounds the chamber; and  
supplying inert gas into the chamber,  
wherein a displacement is generated between the chamber and the closed vessel.

80. (Previously Added) The method according to claim 79, further comprising measuring a positional relationship between a reference member and the chamber, and controlling a displacement mechanism based on a measurement result.

81. (Previously Added) A device manufacturing method comprising the steps of:  
exposing a member to be processed by using an exposure apparatus and the gas  
replacement method defined in claim 79; and  
developing the exposed member in order to manufacture the device.

82. (Previously Added) An exposure apparatus comprising:  
a chamber which incorporates an optical element;  
a closed vessel which surrounds said chamber; and  
a pump for reducing an internal pressure of said chamber,  
wherein said chamber is supported by a supporting member and said closed vessel  
is coupled to the supporting member via a movable displacement adjusting member for  
absorbing a displacement,  
wherein the movable displacement adjusting member includes a bellows.

83. (Previously Added) A device manufacturing method comprising the steps of:  
exposing a member to be processed by the exposure apparatus defined in claim  
82; and  
developing the exposed member in order to manufacture the device.

84. (Previously Added) An exposure apparatus comprising:  
a chamber which incorporates an optical element;

a closed vessel which surrounds said chamber; and  
    a pump for reducing an internal pressure of said chamber,  
    wherein said chamber is supported by a supporting member, and said closed vessel is coupled to the supporting member via a movable displacement adjusting member for absorbing a displacement,

    wherein the apparatus further comprises a second movable displacement adjusting member for adjusting deformation of said closed vessel, and

    said second movable displacement adjusting member holds a transmission window, said transmission window being held at a predetermined positional relationship with respect to the optical element in the chamber.

85. (Previously Added) The apparatus according to claim 84, wherein the movable displacement adjusting member includes a bellows.

86. (Previously Added) The apparatus according to claim 84, wherein said second movable displacement adjusting member includes a bellows.

87. (Previously Added) A device manufacturing method comprising the steps of:  
    exposing a member to be processed by the exposure apparatus defined in claim 84; and  
    developing the exposed member in order to manufacture the device.

88. (Currently Amended) An exposure apparatus comprising:

a chamber which incorporates an optical element;

a closed vessel which surrounds the chamber; and

a member which supports the chamber,

wherein the member is coupled to the closed vessel via a ~~movable displacement~~

~~adjusting member~~ deformable member, and

wherein the member has a region portion which passes through the closed vessel.

89. (Previously Added) The apparatus according to claim 88, further comprising a pump for reducing an internal pressure of the closed vessel.

90. (Currently Amended) The apparatus according to claim 88, wherein the ~~movable displacement~~ adjusting member deformable member includes a bellows.

91. (Previously Added) The apparatus according to claim 88, further comprising a hole for allowing the chamber and the closed vessel to communicate with each other.

92. (Previously Added) The apparatus according to claim 91, wherein the internal pressure of the chamber and the internal pressure of the closed vessel are controlled to have substantially the same internal pressure by the communication via the hole.

93. (Previously Added) A device manufacturing method comprising the steps of:  
exposing a member to be processed by the exposure apparatus defined in claim  
88; and  
developing the exposed member in order to manufacture the device.

94. (Previously Added) An exposure apparatus comprising:

a chamber which incorporates an optical element;  
a closed vessel which surrounds the chamber; and  
a member which supports the chamber,  
wherein the supporting member is coupled to the closed vessel via a bellows.

95. (Previously Added) The apparatus according to claim 94, further comprising a pump  
for reducing an internal pressure of the closed vessel.

96. (Previously Added) The apparatus according to claim 94, wherein the supporting  
member has a region which passes through the closed vessel and supports the chamber.

97. (Previously Added) The apparatus according to claim 94, further comprising a hole  
for allowing the chamber and the closed vessel to communicate with each other.

98. (Previously Added) The apparatus according to claim 97, wherein the internal pressure of the chamber and the internal pressure of the closed vessel are controlled to have substantially the same internal pressure by the communication via the hole.

99. (Previously Added) A device manufacturing method comprising the steps of:  
exposing a member to be processed by the exposure apparatus defined in claim 94; and  
developing the exposed member in order to manufacture the device.

100. (Cancelled)

101. (Cancelled)